## Vorlesungsverzeichnis 21F

Erstellungsdatum: 24.04.2024 22:52

Zürcher Hochschule der Künste Zürcher Fachhochschule

LOC Technology 2: Introduction Fotocluster

Angebot für Bisheriges Studienmodell > Fine Arts > Master Fine Arts > Master Fine Arts

Nummer und Typ MFA-MFA-Te.21F.002 / Moduldurchführung

Modul Technology:

Veranstalter Departement Fine Arts

Leitung Jyrgen Ueberschär, Conradin Frei

Anzahl Teilnehmende maximal 11

**ECTS** 1 Credit

Voraussetzungen Course language: German/English

Lehrform Seminar, group and individual tutorials

Zielgruppen MA Fine Art students only

Not open for exchange-students

Lernziele / Kompetenzen

- Printing: inkjet printing / chromira printing, including printing software: ImagePrint
- Scanning: high-end imacon scanning / epson flatbed scanning, including scanning software: FlexColor & Silverfast

Inhalte

This module dives into the technical possibilities in and around the Fotocluster and helps to understand the typical photographic workflow used in the ZHdK working environment. It offers an overview of the spatial and technical possibilities with a slight hands-on approach in inkjet printmaking and slide scanning:

- Printing: inkjet printing / chromira printing, including printing software: ImagePrint
- Scanning: high-end imacon scanning / epson flatbed scanning, including scanning software: FlexColor & Silverfast

Please bring your own slides (if available) for scanning and highres digital files for large format printing. Basic Photoshop knowledge is required!

About the lecturers:

Conradin Frei (\*1983) studied at the ZHdK, majoring in photography. Since 2010 freelance photographer for magazines, architecture offices, museums and galleries. He is currently working on the realisation of his first book publication, which will be published in 2021.

Jyrgen Ueberschär (\*1978) studied media art from 2002-2008 at the University of Art and Design Karlsruhe (HfG/ZKM) with Lois Renner and Elger Esser and with Jürgen Klauke at the Academy of Media Arts Cologne. In his photography, installations and film sequences, Ueberschär develops spatial scenarios at the interface between reality and fiction. He has had numerous solo and group exhibitions in Germany, Holland, Spain, Korea, Italy, France and China. Workshops and lectures, among others at the Academy of Art Nuremberg and the Musée de l'Elysée Lausanne.

Leistungsnachweis / Testatanforderung

Mandatory attendance (100%); active participation

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Termine Time: 09:00 - 17:00 o'clock

CW 13: 29 / 30 / 31 March, 01 April

Bewertungsform bestanden / nicht bestanden